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Electronic structure investigation of Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$ by soft x-ray emission spectroscopy


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The electronic structures of epitaxially grown films of Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$ have been investigated by bulk-sensitive soft x-ray emission spectroscopy. The measured high-resolution Ti L, C K, Al L, Si L, and Ge M emission spectra are compared with ab initio density-functional theory including core-to-valence dipole matrix elements. A qualitative agreement between experiment and theory is obtained. A weak covalent Ti-Al bond is manifest by a pronounced shoulder in the Ti L emission of Ti$_3$AlC$_2$. As Al is replaced with Si or Ge, the shoulder disappears. For the buried Al and Si layers, strongly hybridized spectral shapes are detected in Ti$_3$AlC$_2$ and Ti$_3$SiC$_2$, respectively. As a result of relaxation of the crystal structure and the increased charge-transfer from Ti to C, the Ti-C bonding is strengthened. The differences between the electronic structures are discussed in relation to the bonding in the nanolaminates and the corresponding change of materials properties.

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I. INTRODUCTION

Recently, the interest in nanolaminated ternary $M_{n+1}AX_n$ (denoted 211, 312, and 413, where $n = 1$, 2, and 3, respectively) carbides and nitrides, so-called MAX phases, has grown significantly. Here, $M$ is an early transition metal, $A$ is a $p$ element, usually belonging to the groups IIIA and IVA, and $X$ is either carbon or nitrogen. The large interest is due to the fact that these layered materials exhibit a unique combination of metallic and ceramic properties, including high strength and stiffness at high temperatures, resistance to oxidation and thermal shock, as well as high electrical and thermal conductivity. These unusual macroscopic properties are closely related to the electronic and structural properties of the constituent atomic layers on the nanoscale.

This family of compounds has a hexagonal structure with nearly close-packed layers of the $M$ elements interleaved with square-planar slabs of pure $A$ elements, where the $X$ atoms fill the octahedral sites between the $M$ atoms. However, the $A$ elements are also located at the center of trigonal prisms that are larger than the octahedral sites and thus better accommodate the $A$ atoms. Among the 312 phases, there are three carbides which belong to this family, namely, Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$. Figure 1 shows the crystal structure of the 312-phases.

Up to now, the most studied MAX material is Ti$_3$SiC$_2$, which consists of hexagonal layers stacked in the repeated sequence of Si-Ti$_{II}$-C-Ti$_{II}$-C-Ti$_{III}$, where the unit cell consists of two formula units. Ti atoms can occupy either of two different sites; Ti$_{III}$ which has both C and Si neighbors and Ti$_{II}$ which only has C neighbors. Most of the research on Ti$_3$SiC$_2$ has incorporated processing and mechanical properties of sintered bulk compounds. However, in many technological applications where, e.g., high melting points, corrosion resistance, electrical and thermal conductivity as well as low-friction gliding properties are required, high-quality thin film coatings are more useful than bulk materials. Although MAX phases and related compounds have been studied previously, a full knowledge of why these materials obtain certain properties has not yet been obtained. One reason for why a complete understanding is lacking lies in the difficulties in obtaining accurate electronic structure measurements of internal atomic layers.

Previous experimental investigations of the electronic structure of Ti$_3$SiC$_2$ include valence-band x-ray photoemis-

![FIG. 1. (Color online) The hexagonal crystal structure of the Ti$_3$AC$_2$ phases. The Ti atoms have two different sites, denoted Ti$_{II}$ and Ti$_{III}$. Every fourth layer in the 312-phases is interleaved with layers of the pure A-group element.](image-url)
sion (XPS).\textsuperscript{6–8} However, XPS is a surface-sensitive method which is not element specific. Theoretically, it has been shown by \textit{ab initio} band structure calculations that there should be significant differences between the partial density-of-states (DOS) of Ti and C when Si is exchanged for another A element.\textsuperscript{9} Thus, if it would be possible to perform bulk-sensitive and element-specific electronic structure measurements and compare them to \textit{ab initio} band structure calculations for a series of compounds with different A elements, one could obtain the most reliable information about the differences in the internal electronic structure of the buried layers.

In this paper, we investigate and compare the electronic structures of Ti\textsubscript{3}AlC\textsubscript{2}, Ti\textsubscript{3}SiC\textsubscript{2}, and Ti\textsubscript{3}GeC\textsubscript{2} with each other, using the bulk-sensitive and element-specific soft x-ray emission (SXE) spectroscopy method with selective excitation energies around the Ti 2p, C 1s, Al 2p, Si 2p, and Ge 3p thresholds. The SXE technique is more bulk sensitive than electron-based techniques such as XPS and x-ray absorption spectroscopy (XAS). Due to the involvement of both valence and core levels, each kind of atomic element can be probed separately by tuning the excitation energy to the appropriate core edge. The SXE spectroscopy follows the dipole selection rule and conserves the charge neutrality of the probed system. This makes it possible to extract both elemental and chemical near ground-state information of the electronic structure. The SXE spectra are interpreted in terms of partial valence band DOS weighted by the transition matrix elements. The main objective of the present investigation is to systematically study the nanolaminated internal electronic structures and the influence of hybridization among the constituent atomic planes in the Ti\textsubscript{3}AC\textsubscript{2} materials using the combination of x-ray emission spectroscopy and density-functional calculations. By comparing the partial electronic structures of the three 312 systems, important information about the bonding is achieved, creating a basis for the understanding of the unusual materials properties.

II. EXPERIMENT

A. X-ray emission measurements

The SXE measurements were performed at the undulator beamline I511-3 at MAX II (MAX-lab National Laboratory, Lund University, Sweden), comprising a 49-pole undulator and a modified SX-700 plane grating monochromator.\textsuperscript{10} XAS spectra at the Ti 2p and C 1s edges were recorded in total electron yield mode by measuring the sample drain current as a function of the photon energy of the incident monochromatized synchrotron radiation. The SXE spectra were normalized to the photocurrent from a clean gold mesh introduced into the synchrotron radiation beam in order to correct for intensity variations of the incident x-ray beam. During the SXE measurements at the Ti 2p and C 1s edges, the resolution of the beamline monochromator was about 0.1 eV.

The SXE spectra were recorded with a high-resolution Rowland-mount grazing-incidence grating spectrometer\textsuperscript{11} with a two-dimensional detector. The Ti L and C K x-ray emission spectra were recorded using a spherical grating with 1200 lines/mm of 5 m radius in the first order of diffraction. The Al L, Si L, and Ge M spectra were recorded using a grating with 300 lines/mm, 3 m radius in the first order of diffraction. During the SXE measurements at the Ti 2p, C 1s, Al 2p, Si 2p, and Ge 3p edges, the resolutions of the beamline monochromator were 1.6, 1.0, 0.3, 0.2, and 0.4 eV, respectively. The SXE spectra were recorded with spectrometer resolutions 0.7, 0.2, 0.2, 0.2, and 0.2 eV, respectively. All the measurements were performed with a base pressure lower than 5 \texttimes{} 10\textsuperscript{−9} Torr. In order to minimize self-absorption effects,\textsuperscript{12} the angle of incidence was 30° from the surface plane during the emission measurements. The x-ray photons were detected parallel to the polarization vector of the incoming beam in order to minimize elastic scattering.

B. Deposition of Ti\textsubscript{3}AC\textsubscript{2} (A = Al, Si, Ge) films

The MAX-phase thin films were deposited by dc magnetron sputtering (base pressure \textsim{} 5 \texttimes{} 10\textsuperscript{−10} Torr) from elemental targets of Ti and C, and Al, Si or Ge in an argon discharge pressure of 4 mTorr. \textalpha{}-Al\textsubscript{2}O\textsubscript{3}(0001) was used as substrate. However, to promote a high quality growth of the MAX phases, a 200 Å thick seed layer of TiC\textsubscript{0.7}(111) was initially deposited. The Ti\textsubscript{3}AlC\textsubscript{2} film was 5000 Å thick, while the Ti\textsubscript{3}SiC\textsubscript{2} and Ti\textsubscript{3}GeC\textsubscript{2} films were 2000 Å thick. For further details on the synthesis process, the reader is referred to Refs. 13–15.

Ordinary \theta{}-\theta{} diffractograms of the deposited films are shown in Fig. 2. As observed, the peaks originate from Ti\textsubscript{3}AC\textsubscript{2}(0000) together with peaks from the TiC(111) seed-layer and the \textalpha{}-Al\textsubscript{2}O\textsubscript{3}(0006) substrate. In Fig. 2(a), small contributions of Ti\textsubscript{3}Al and Ti\textsubscript{3}AlC can also be observed, and in Fig. 2(b), a small peak from Ti\textsubscript{3}Si\textsubscript{1}C\textsubscript{6} (all marked with arrows). The low intensities of the small additional peaks show that the films mainly consist of single-phase MAX phases. Furthermore, the fact that the diffractograms only
show Ti$_2$AC$_2$ of {0001}-type suggests highly textured or epitaxial films. X-ray pole figures verified that the growth indeed was epitaxial, and determined the relation to Ti$_3$AC$_2$(000)/TiC(111)//Al$_2$O$_3$(000) with an in-plane orientation of Ti$_3$AC$_2$(210)/TiC(110)//Al$_2$O$_3$(210). The epitaxial growth behavior has also been documented by transmission electron microscopy (TEM).\textsuperscript{16-20} XPS-analysis depth profiles of the deposited films within the present study using a PHI Quantum instrument, showed after 60 seconds of Ar sputtering a constant composition without any contamination species. From the diffractograms in Fig. 2, the values of the c-axis were determined to be 18.59 Å, 17.66 Å, and 17.90 Å for the Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$ MAX phases, respectively.

III. COMPUTATIONAL DETAILS

A. Calculation of the x-ray emission spectra

The x-ray emission spectra were computed within the single-particle transition model using by the full potential linearized plane wave (FPLAPW) method.\textsuperscript{21} Exchange and correlation effects were taken into account through the generalized gradient approximation (GGA) as parametrized by Perdew, Burke, and Ernzerhof.\textsuperscript{22} A plane wave cutoff, corresponding to $R_{MT}\ast k_{max}=8$, was used for all the investigated phases. The charge density and potentials were expanded up to $\ell=12$ inside the atomic spheres, and the total energy was converged with respect to the Brillouin zone integration.

The emission intensity $I_c$ for a hole created in the $c$th core shell can be written in cgs units as\textsuperscript{23}

$$I_c(E) = \frac{2e^2\hbar}{mc^3} F_c(E), \quad E < E_F,$$

where $F_c(E)$ represents the spectral distribution given by\textsuperscript{23-25}

$$F_c(E) = \frac{2m}{3\hbar^2} \left| \langle \phi_{LM}(\vec{r}) \phi_{c}\rangle \right|^2 \delta(E - E_{F}).$$

In the above equation $\phi_{LM}$ is the core wave function, $\vec{r}$ the wave vector of the incident photon, $\vec{q}$ the polarization tensor, and $E_{F}$ and $\phi_{c}$ are the energy and the wave function of the $j$th valence band at vector $\vec{k}$. The energy of the emitted photon is represented by $\omega=E-E_c$, where $E_c$ is the core energy level. The emission spectra were computed using by the electric-dipole approximation which means that only the transitions between the core states with orbital angular momentum $\ell$ to the $\ell+1$ components of the valence bands were considered. The core-hole lifetimes used in the calculations were 0.73 eV, 0.27 eV, 0.45 eV, 0.5 eV, and 2.0 eV, for the Ti 2p, C 1s, Si 2p, Al 2p, and Ge 3p edges, respectively. A direct comparison of the calculated spectra with the measured data was finally achieved by including the instrumental broadening in the form of Gaussian functions corresponding to the experimental resolutions (see experimental section II A). The final state lifetime broadening was accounted for by a convolution with an energy-dependent Lorentzian function with a broadening increasing linearly with the distance from the Fermi level ($E_F$) according to the function $a+b(E-E_f)$, where the constant $a$ is in units of eV $b$ is dimensionless.\textsuperscript{26} For Ti, C, Al, and Si $a$ was 0.01 eV and $b$ was 0.05. For Ge, a variable lifetime broadening of the valence band was not feasible since the expanded energy region also contains the 3d core levels.

B. Balanced crystal orbital overlap population (BCOOP)

In order to study the chemical bonding of the Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$ compounds, we also calculated the BCOOP function by using the full potential linear muffin-tin orbital (FPLMTO) method.\textsuperscript{27} In these calculations, the muffin tins are kept as large as possible (without overlapping one another), so that the muffin tins fill about 66% of the total volume. To ensure a well-converged basis set, a double basis set with a total of four different $\kappa^2$ values is used. For Ti, we include the 4s, 4p, and 3d as valence states. To reduce the core leakage at the sphere boundary, we also treat the 3s and 3p core states as semicore states. For Al and Si, 3s, 3p, and 3d are taken as valence states. For Ge, we used semicore 3d and valence 4s, 4p, and 4d basis functions. The resulting basis forms a single, fully hybridizing basis set. This approach has previously proven to give a well-converged basis.\textsuperscript{28} For the sampling of the irreducible wedge of the Brillouin zone, we use a special-k-point method\textsuperscript{29} and the number of $k$ points we used is 216 for the self-consistent total energy calculation. In order to speed up the convergence, a Gaussian broadening of width 20 mRy is associated with each calculated eigenvalue.

IV. RESULTS

A. Ti L x-ray emission spectra

Figure 3 (top) shows Ti L$_{2,3}$ SXE spectra of Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$ excited at 458 eV, 459.8 eV, 463.5 eV, and 477 eV photon energies, corresponding to the 2p$_{1/2}$ and 2p$_{1/2}$ absorption maxima (vertical bars in the XAS spectra) and nonresonant excitation. The XAS measurements have been made to identify the resonant excitation energies for the SXE measurements. For comparison of the SXE spectral profiles, the measured spectra are normalized to unity and are plotted on a common photon energy scale and relative to the $E_F$ using the 2p$_{1/2}$ core-level XPS binding energy of 460.8 eV in Ti$_3$SiC$_2$.\textsuperscript{5} The main L$_3$ and L$_2$ emission lines are observed at $\approx$8.7 eV and $\approx$2.5 eV on the relative energy scale. Contrary to pure Ti, a peak structure is also observed at $\approx$16.2 eV. This is the result of Ti-C hybridization. As observed, the Ti L$_{2,3}$ SXE spectra appear rather delocalized (wide bands) which makes electronic structure calculations suitable for the interpretation of the spectra. Calculated spectra for the two Ti sites (Ti$_1$ and Ti$_2$), their sum and difference are also shown in the lower part of Fig. 3. Although SXE is a site-selective spectroscopy, separate contributions from the two crystallographically different Ti sites are not experimentally resolved due to their negligible energy difference. For resonant excitation at the 2p$_{1/2}$ absorption maximum (463.5 eV), the L$_2$ emission resonates and the L$_3$/L$_2$ ratio is close to

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For nonresonant, continuum excitation far above the 2\(p\) thresholds, the \(L_3/L_2\) ratio is 6:1. In general, nonresonant \(L_3/L_2\) emission ratios in 3\(d\) transition metals have been observed to be higher than the statistical weight of atomic levels due to the opening of the Coster-Kronig process at the 2\(p\) threshold. The Coster-Kronig decay from the 2\(p\)\(1/2\) core-level leads to a shorter lifetime and a larger Lorentzian width for the 2\(p\)\(1/2\) core state than for the 2\(p\)\(3/2\) state. For a clear comparison between the experimental and calculated spectral structures, the nonresonant emission spectra excited at 477 eV are suitable since they resemble the occupied electronic states, and resonant phenomena are avoided. In the fitting procedure to the 477 eV SXE spectra, we employed the experimental values for the \(L_3/L_2\) ratio of 6:1 and the \(L_2,3\) peak splitting of 6.2 eV which is larger than our calculated \textit{ab initio} spin-orbit splitting of 5.7 eV. Note that the Ti 2\(p\) peak splitting obtained from XAS, XPS (Ref. 30) and SXE (Ref. 31) spectra are not exactly the same due to screening and different number of electrons in the final states. The spectral weight at the \(E_F\) is significantly higher for the calculated Ti\(\text{II}\) atoms which are directly bonded to the A atoms than for the Ti\(\text{I}\) atoms. This suggests that the Ti\(\text{II}\) atoms contribute more to the conductivity than the Ti\(\text{I}\) atoms. The Ti\(\text{II}-\text{Ti}\) difference spectra are a measure of the difference in the electronic structure and hence, the bonding strength between the 3\(d\) states of the Ti\(\text{II}\) and Ti\(\text{I}\) atoms and the \(s,\ p\), \(d\) states of the A element. The largest difference in the Ti\(\text{II}-\text{Ti}\) bonding is observed for the Ti\(\text{III}\)\(\text{AlC}_2\) system. The most significant difference between the studied systems is the pronounced shoulder (observed both in experiment and calculations) in Ti\(\text{III}\)\(\text{AlC}_2\) (indicated by the arrow at the top in Fig. 3) which is not observed in the other systems. This shoulder has a splitting from the main line of 1.5 eV. From the calculated band structure, the nature of this shoulder is related to a series of flat bands (not shown) with Ti 3\(d\) character which are shifted towards the \(E_F\).

### B. C K x-ray emission spectra

Figure 4 (top) shows experimental C K SXE spectra of Ti\(\text{III}\)\(\text{AlC}_2\), Ti\(\text{III}\)\(\text{SiC}_2\), and Ti\(\text{III}\)\(\text{GeC}_2\) excited at 284.8 eV and 310 eV photon energies. The XAS measurements have been
made to identify the resonant excitation energy (vertical bar) for the SXE measurements. The experimental spectra are plotted both on a photon energy scale and relative to the $E_F$ using the C 1s core-level XPS binding energy of 281.83 eV in Ti$_3$SiC$_2$. Calculated spectra are shown at the bottom of Fig. 4. The main peak at $-2.6$ eV has shoulders on both the low- and high-energy sides at $-4.2$ eV and $-2$ eV. The agreement between the experimental and calculated spectra is good although the low-energy shoulder at $-4.2$ eV is more pronounced in the experiment. The main peak and the shoulders correspond to the occupied C 2$p$ orbitals hybridized with the Ti 3$d$ and $A$ spd bonding and antibonding orbitals of the valence bands. As observed both in the experimental and calculated spectra, the high-energy shoulder is less pronounced in Ti$_3$AlC$_2$ in comparison to Ti$_3$SiC$_2$ and Ti$_3$GeC$_2$ which have similar spectral shapes. It should also be noted that the chemical shift between Ti$_3$AlC$_2$ and the other two studied compounds is very small both in the experiment and in the theoretical work. Experimentally, the upward chemical shifts for Ti$_3$AlC$_2$ and Ti$_3$SiC$_2$ are both $-0.05$ eV while the theory predicts a somewhat larger upward shift of $+0.24$ eV for Ti$_3$AlC$_2$, in contrast to observations.

C. Al $L$ x-ray emission spectra

Figure 5 (top) shows an experimental Al $L_{2,3}$ SXE spectrum of Ti$_3$AlC$_2$ measured nonresonantly at $120$ eV photon energy. The experimental spectrum is plotted on a photon energy scale and relative to the $E_F$ using the Al $2p_{3/2}$ core-level XPS binding energy of $71.9$ eV for Ti$_3$AlC$_2$. A calculated spectrum with the $L_{2,3}$ spin-orbit splitting of $0.438$ eV and the $L_3/L_2$ ratio of $2:1$ is shown at the bottom. Comparing the experimental and calculated spectra, it is clear that the main peak at $-3.9$ eV of the SXE spectrum is dominated by $3s$ final states. The partly populated 3$d$ states form the broad peak structure close to the Fermi level and participate in the Ti-Al bonding in Ti$_3$AlC$_2$. Al 3$p$ states dominate in the upper part of the valence band but do not directly contribute to the $L_{2,3}$ spectral shape since they are dipole forbidden. The contribution of the Al 3$p$ states can be probed using SXE at the Al K-edge. For the Al $L_{2,3}$ SXE spectrum, the valence-to-core matrix elements are found to play an important role to the spectral shape. In contrast to Al $L_{2,3}$ SXE spectra of pure Al, which have a sharp and dominating peak structure within $1$ eV below $E_F$, the Al $L_{2,3}$ SXE spectrum of Ti$_3$AlC$_2$ has a strongly modified spectral weight towards lower energy. A similar modification of the Al $L_{2,3}$ SXE spectral shape has also been observed in the metal aluminides. Comparing the spectral shape to the aluminides, the appearance of the broad low-energy shoulder around $-6$ eV in the Al $L_{2,3}$ SXE spectrum of Ti$_3$AlC$_2$ can be attributed to the formation of hybridized Al 3$s$ states produced by the overlap of the Ti 3$d$ orbitals. This interpretation is supported by our first-principle calculations.

D. Si $L$ x-ray emission spectra

Figure 6 (top) shows an experimental Si $L_{2,3}$ SXE spectrum of Ti$_3$SiC$_2$ measured nonresonantly at $120$ eV photon energy. The experimental spectrum is plotted on a photon energy scale and relative to the $E_F$ using the Si $2p_{3/2}$ core-level XPS binding energy of $99.52$ eV for Ti$_3$SiC$_2$. A calcu-
lated spectrum with the $L_{2,3}$ spin-orbit splitting of 0.646 eV and the $L_2/L_1$ ratio of 2:1 is shown at the bottom. In the Si spectrum, the $3s$-character is concentrated to the bottom of the valence band with the main peak at $-7$ eV. The shift of the main peak towards lower energy is related to the extra valence electron in Si in comparison to Al. As in the case of Al, the partly populated Si $3d$ states in the upper part of the valence band also participate in the Ti-Si bonding in Ti$_3$SiC$_2$. The Si $3p$-states in the upper part of the valence band do not directly contribute to the $L_{2,3}$ spectral shape since they are dipole forbidden, but can be probed using SXE at the Si $K$-edge. The valence-to-core matrix elements are found to play an important role to the spectral shape of the Si $L_{2,3}$ SXE spectrum. Notably, the observed spectral shape of the Si $L_{2,3}$ SXE spectrum of Ti$_3$SiC$_2$ appears rather different from single crystal bulk Si which has a pronounced double structure.\textsuperscript{33,34} On the other hand, the spectral shape of the Si $L_{2,3}$ SXE spectrum of Ti$_3$SiC$_2$ is similar to what has been observed for the metal silicides.\textsuperscript{35,36} Comparing the Si $L_{2,3}$ SXE spectrum of Ti$_3$SiC$_2$ to the silicides, the low-energy shoulder on the main peak around $-8.5$ eV can be attributed to the formation of hybridized Si $3s$ states produced by the overlap of the Ti $3d$ states, which is also supported by our theory.

E. Ge $M$ x-ray emission spectra

Figure 7 (top) shows experimental Ge $M_{2,3}$ SXE spectra of Ti$_3$GeC$_2$ measured nonresonantly at 150 eV (27 eV above the $3p_{3/2}$ absorption maximum) and 165 eV photon energies. The experimental spectra are plotted on a photon energy scale and relative to the $E_F$ using the Ge $3p_{1/2}$ core-level XPS binding energy of 125.5 eV for Ti$_3$GeC$_2$.\textsuperscript{57} A calculated spectrum is shown at the bottom, both for the $4sd$ valence band (full curve) and the $3d$ core levels (dashed curve). It should be noted that the measured Ge $M_{2,3}$ emission is two orders of magnitude weaker than the Al and Si $L_{2,3}$ emission which makes the measurements more demanding. The shallow $3d$ core levels shown at the left consists of two peaks from the Ge $M_{4,5} \rightarrow M_1$ and $M_1 \rightarrow M_2$ ($3d \rightarrow 3p_{3/2,1/2}$) transitions with energies of $-32.7$ and $-29.1$ eV relative to the $E_F$. The observed Ge $M_{2,3}$ spin-orbit splitting of 3.6 eV (Ref. 38) is somewhat smaller than the calculated value of 4.3 eV and the calculated $3d$ core levels (dashed curve) are also closer to the $E_F$ by 3.9 eV. The measured $M_3/M_2$ intensity ratio of about 6/5:1 differs from the statistical ratio of 2:1. The intensity of the $3d$ core levels was divided by a factor of 10 to match the experimental data. In addition to the calculated DOS, the overlap by the matrix elements play an important role for the intensity of the shallow $3d$ core levels. However, the general agreement between the measured and calculated spectral shapes is good.

The $4sd$ valence band within 10 eV from the $E_F$ consists of a double structure with $M_3$ and $M_2$ emission peaks observed at $-12$ eV and $-8$ eV, respectively. This double structure is significantly different from the three-peak structure observed in the $M_{2,3}$ emission of bulk Ge.\textsuperscript{36} In bulk Ge, the $4sd$ DOS of the $M_3$ and $M_2$ emission bands are not only separated by the spin-orbit splitting of 3.6 eV, but are also split up into two subbands, separated by 3.5 eV (as in the case of single crystal bulk Si). The result is a triple structure in the valence band of bulk Ge where the upper and lower emission peaks are solely due to $M_3$ and $M_2$ emissions, respectively, while the main middle peak is a superposition of both $M_3$ and $M_2$ contributions. On the contrary, the Ge $4sd$ DOS in Ti$_3$GeC$_2$ consists of a single peak structure with more spectral weight towards the $E_F$. A shift of peak structures towards the $E_F$ in comparison to bulk Ge has been observed in Ge $K$ emission (probing the $4p$ valence states) of the metal germanides.\textsuperscript{40} The Ge $4p$ states in the upper part of the valence band are not directly observed in the $M_{2,3}$ emission spectra since they are dipole forbidden but are indirectly reflected due to the mixing of $s$ and $p$ states in the solid. Finally, we note that at 150 eV excitation energy, a weak energy loss structure is superimposed onto the valence band. This weak loss structure, tracking 30 eV below the excitation energy, originates from localized $dd$ excitations from the shallow $3d$ core level. At the excitation energy of 165 eV (42 eV above the $3p_{3/2}$ absorption maximum) the dispersing loss structure does not affect the spectral profile of the valence band.
By relaxing the cell parameters of the Ti$_3$AC$_2$ phases (A = Al, Si, and Ge), it was possible to calculate the equilibrium c axis. They were determined to be 18.64 Å, 17.68 Å, and 17.84 Å for Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$, respectively. These values are in excellent agreement with the experimental values in Sec. II B. In order to analyze the chemical bonding, we show in Fig. 8 the calculated BCOOP of the three Ti$_3$AC$_2$ systems. This analysis provides more information about the bonding and is the partial DOS weighted by the balanced overlap population. The BCOOP is a function which is positive for bonding states and is negative for antibonding states. The strength of the covalent bonding can be determined by summing up the area under the BCOOP curve. The energy position of the peaks also gives an indication of the strength of the covalent bonding. First, comparing the areas under the BCOOP curves and the distances of the main peaks around $-3$ eV from the $E_F$, it is clear that the Ti 3d-C 2p bonds are generally much stronger than the Ti 3d-A element p bonds. Additional bonding occurs around $-10$ eV with an important Ti 3d-C 2s overlap, corresponding to $-16.2$ eV when the $L_{2,3}$ peak splitting is taken into account (see Fig. 3). The areas under the Ti$_{III}$-C curves are larger than for the Ti$_{II}$-C curves, which indicates stronger bonds. This implies that the Ti$_{III}$ atoms lose some bond strength to the nearest neighbor A atoms, which to some degree is compensated with a stronger Ti$_{II}$-C bond. This observation implies that the Ti-C bonds in principle can be stronger in the Ti$_3$AC$_2$ phases than in TiC. This can also be observed in our calculated value for the Ti-C bond length which is 2.164 Å for TiC, in good agreement with the experimental value of 2.165 Å. For comparison, the calculated shorter Ti$_{III}$-C bond lengths for Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$ are 2.086 Å, 2.097 Å, and 2.108 Å, respectively, indicating stronger bonds. Second, comparing the BCOOP curves between the three systems show that the Ti$_{III}$-C BCOOP curves of Ti$_3$AlC$_2$ are the most intense and are somewhat shifted towards the $E_F$. Third, the Ti$_{III}$3d-Al 3p BCOOP peak is located at about $-1$ eV below $E_F$ (indicated by the arrow), while the Ti$_{III}$3d-Si 3p and Ti$_{III}$3d-Ge 4p BCOOP peaks are located around $-2$ eV below the $E_F$. This is an indication that the Ti$_{III}$3d-Al 3p bond is weaker than the Ti$_{III}$3d-Si 3p and Ti$_{III}$3d-Ge 4p bonds which has also been confirmed by the differences in bond lengths. Our calculated Ti$_{II}$-A bond lengths for Ti$_3$AlC$_2$, Ti$_3$SiC$_2$, and Ti$_3$GeC$_2$ are 2.885 Å, 2.694 Å, and 2.763 Å, respectively. Fourth, the calculated C 2p-A s overlaps (not shown) have significantly different shapes in comparison to the other overlaps which is an indication that this bond has a weaker covalent character.

For the Al $L_{2,3}$ SXE spectrum of Ti$_3$AlC$_2$ presented in Sec. IV C, the BCOOP calculations confirm that the broad low energy shoulder at $-6$ eV can be attributed to bonding Al 3s orbitals hybridized with Ti 3d and C 2p orbitals. The main peak at $-3.9$ eV corresponds to hybridization with bonding C 2p orbitals and the shoulder at $-3$ eV is due to both bonding Ti 3d and C 2p orbitals. The broad structure around $-1$ eV is due to bonding Ti 3d orbitals and antibonding C 2p orbitals. In the case of the Si $L_{2,3}$ SXE spectrum of Ti$_3$SiC$_2$ presented in Sec. IV D, the shoulder at $-8.5$ eV is attributed to hybridization with bonding Ti 3d orbitals and antibonding C 2p orbitals. The peak structure at $-3.5$ eV corresponds to hybridization with bonding Ti 3d orbitals and antibonding C 2p orbitals while the wiggles between $-1$ eV and $-3$ eV are related to bonding Ti 3d and C 2p orbitals of varying strength.

V. DISCUSSION

The present results provide understanding of the electronic structure and hence the bonding in the Ti$_3$AC$_2$ phases (A=Al, Si, Ge) as a basis for an understanding of their unusual material properties. Our SXE investigation confirms that the Ti 3d-A $p$ bonding is different in Ti$_3$AlC$_2$ in comparison to Ti$_3$SiC$_2$ and Ti$_3$GeC$_2$. The calculations show that the double peak in the Ti $L_{2,3}$ SXE spectrum mainly originate from the Ti$_{III}$ atoms. As a consequence of increasing the $c$ axis of the hexagonal 312 unit cell to its equilibrium length (i.e., increasing the $c$ distance in the $z$ direction in Fig. 1) and the simultaneous symmetry breaking of the $A$-element mirror plane in the trigonal prisms, the Ti$_{III}$3d-A $p$ bond is shortened and the Ti$_{III}$3d-C $p$ bond is lengthened. In the case of Ti$_3$SiC$_2$
and Ti$_3$GeC$_2$, the splitting of the double-structure stemming from the Ti$_{II}$ atoms in the calculated Ti 3$d$ DOS is considerably smaller (~0.5 eV) than for Ti$_3$AlC$_2$ (1.5 eV). As a consequence, no double-peak structure is resolved and observed in the sum of the Ti$_1$ and Ti$_{II}$ peak contributions for Ti$_3$SiC$_2$ and Ti$_3$GeC$_2$. The significantly larger peak splitting in Ti$_3$AlC$_2$ is related to the difference in bonding character as shown by the BCOOP analysis in Fig. 8. This implies that the Ti$_{III}$-Al 3$p$ bond is less covalent than the Ti$_{III}$-3$d$-Si 3$p$ and Ti$_{III}$-3$d$-Ge 3$p$ bonds. Our results confirm the general trend in the Ti-A bond strength where the Ti-Si and Ti-Ge bonds are stronger than the Ti-Al bond. As the valence electron population of the A element is increased by replacing the partly filled valence band of a IIIA element by the isoelectronic valence band of a IVA element, e.g., by replacing Al to Si or Ge, more charge is placed into the Ti-A bond. This is directly reflected in a stronger bond and implies a modulus and electrical conductivity than Ti$_3$AlC$_2$. The BCOOP analysis confirms that the covalent bond. Here, the weaker Ti$_3$AlC$_2$-C bond is generally much stronger than the Ti$_3$SiC$_2$-C 2$p$ bond in another MAX sequence, no double-peak structure is resolved and observed. This provides an important test of the usefulness of theoretical calculations. It also shows that the interpretation of the emission spectra of these materials is best understood as delocalized band states and that excitonic effects are of minor importance.

The analysis of the electronic structures provides increased understanding of the hybridization and chemical bonding of the materials. We find that the Ti-Al bonding in Ti$_3$AlC$_2$ has less covalent character than the Ti-Si bond of Ti$_3$SiC$_2$ and Ti-Ge bond of Ti$_3$GeC$_2$. Emission spectra of Si in Ti$_3$SiC$_2$, Al in Ti$_3$AlC$_2$, and Ge in Ti$_3$GeC$_2$ appear very different from the pure Al, Si, and Ge elements indicating strong hybridization between the A atoms with Ti and C. Changes in the Ti-A bond strength is shown to have direct implications on the Ti-C bonding. Therefore, the A element substitution and corresponding tuning of the valence electron population from the unfilled states of Al to the isoelectronic states in Si and Ge implies that the unusual material properties of these nanolaminated carbide systems can be custom-made by the choice of A element.

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37. Due to screening and charge-transfer from Ge to C, there is a 0.3 eV low-energy shift of the Ge 3p_{3/2} and 3p_{1/2} XPS binding energies in Ti_{3}GeC_{2} (121.4 and 125.5 eV, respectively) in comparison to single-crystal bulk Ge (121.7 and 125.8 eV, respectively).

38. The 3.6 eV splitting in the measured emission spectra is the difference between the 3p_{3/2,1/2} and 3d_{5/2,3/2} spin-orbit splittings observed in XPS, i.e., 4.1–0.5 eV.


